perature and for a time sufficient to remove water from said solution;

(d) altering the surface of said substrate by heating the same at a temperature between about 318° C. to about 1000° C. to melt said alkali metal hydroxide coating on said substrate's surface;

(e) cooling the substrate and rinsing the substrate in a dilute acid solution to neutralize said alkali metal hydroxide;

(f) rinsing the substrate in water;

(g) sensitizing and activating the substrate, and thereafter

(h) immersing said altered substrate in an electrolesss metal plating bath for a time sufficient to deposit a strongly adhering metal layer thereon.

2. A method according to claim **1** wherein said alkali metal hydroxide solution of step (c) consists of about 50 grams of sodium hydroxide dissolved in 100 ml. of water.

3. A method according to claim **2** wherein said coating of an alkali metal hydroxide is deposited on said substrate by heating at a temperature of about 170° C. for a duration of 5 minutes.

4. A method according to claim **3** wherein said surface of said substrate is altered by heating the same to a temperature of about 450° C. to about 500° C.

5. A method according to claim **4** wherein said altered substrate is rinsed in a 20% acid solution selected from the group consisting of HCl, H_2SO_4 and HNO_3, for about 2 minutes.

6. A method according to claim **1** wherein the molten alkali metal hydroxide is maintained at a temperature of about 450° C. to about 500° C.

7. A method of electrolessly depositing a metal onto a surface of a ceramic substrate comprising the steps of:

(a) cleaning the substrate in a hot alkaline cleaning solution;

(b) rinsing the clean substrate in water;

(c) immersing said clean substrate in a molten alkali metal hydroxide;

(d) removing the substrate from said molten alkali metal hydroxide;

(e) cooling the substrate;

(f) rinsing the substrate in a dilute acid solution to neutralize said alkali metal hydroxide;

(g) rinsing the substrate in water to remove acid from said substrate;

(h) sensitizing and activating the substrate, and thereafter,

(i) immersing said altered substrate in an electroless metal plating bath for a time sufficient to deposit a strongly adhering metal film thereon.

8. A method according to claim **7** wherein said alkaline cleaning solution is maintained at a temperature of about 60° C.

9. A method according to claim **7** wherein the molten alkali metal hydroxide is maintained at a temperature in the range of about 318° C. to about 1000° C. and for a duration of about 10 to about 15 minutes.

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